

for 10/712,460

Refine Search**Search Results -**

Terms	Documents
(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay same wafer	14

Database:

US Pre-Grant Publication Full-Text Database

US Patents Full-Text Database

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EPO Abstracts Database

JPO Abstracts Database

Derwent World Patents Index

IBM Technical Disclosure Bulletins

Search:

L3

Refine Search

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<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
side by side			
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L3</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay same wafer	14	<u>L3</u>
<u>L2</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same (delay near1 time)	22	<u>L2</u>
<u>L1</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay	144	<u>L1</u>

END OF SEARCH HISTORY